

PATENT ABSTRACTS OF JAPAN

(11)Publication number : **02-134820**

(43)Date of publication of application : **23.05.1990**

(51)Int.Cl.

H01L 21/304

B08B 3/02

(21)Application number : **63-287725**

(71)Applicant : **HITACHI LTD**
HITACHI ELECTRON ENG
CO LTD

(22)Date of filing : **16.11.1988**

(72)Inventor : **NAKAMURA HISATO**

(54) CLEANING AND DRYING DEVICE

(57)Abstract:

PURPOSE: To obtain a device which can clean and completely dry an object to be treated even with solution of relatively high viscosity attached thereto by providing a first nozzle device which sprays a first cleaning solution to the object to be treated and a second nozzle device which sprays a second cleaning solution to the object to be treated to lower the viscosity of the first cleaning solution.

CONSTITUTION: A device is provided with a spin head 2 to hold, rotate and dry a treatment object 7, a first nozzle device 11 to spray a first cleaning solution to the object 7 to be treated and a second nozzle device 21 to spray a second cleaning solution to lower a viscosity of the first cleaning solution to the treatment object 7. For example, a cleaning and drying device to eliminate a foreign material of photosensitive polyimide attached to a rear side of a wafer 7 is

integrally incorporated in an application device to apply photosensitive polyimide 5 onto the wafer 7. The first nozzle 11 is made to supply pyrrolidine being a solvent of photosensitive polyimide solution as the first cleaning solution from the first cleaning solution supply device 13 through a control valve 15. The second nozzle, 1 is made to supply pure water 22 as the second cleaning solution from a second cleaning solution supply device 23 through a control valve 25.



